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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/088,026	10/08/2003	Janet E. Hails	124-933	4943
23117 75	590 06/13/2005		EXAMINER	
NIXON & VANDERHYE, PC 901 NORTH GLEBE ROAD, 11TH FLOOR			DOTY, HEATHER ANNE	
ARLINGTON,		JK	ART UNIT PAPER NUMBE	
			2813	
			DATE MAILED: 06/13/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Action Summers	10/088,026	HAILS ET AL.	-			
Office Action Summary	Examiner	Art Unit				
	Heather A. Doty	2813				
The MAILING DATE of this communication ap Period for Reply	pears on the cover sheet with the o	orrespondence add:	ress			
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a rep. If NO period for reply is specified above, the maximum statutory period. - Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply be tirely within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE	mely filed ys will be considered timely. the mailing date of this con ED (35 U.S.C. § 133).	nmunication.			
Status	•					
1) Responsive to communication(s) filed on 11 F	ebruary 2005.					
,	s action is non-final.					
3) Since this application is in condition for allows closed in accordance with the practice under			merits is			
Disposition of Claims						
4)⊠ Claim(s) <u>1-18</u> is/are pending in the application	1.		•			
4a) Of the above claim(s) is/are withdra			:			
5) Claim(s) is/are allowed.			:			
6)⊠ Claim(s) <u>1-18</u> is/are rejected.						
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/o	or election requirement.		· · :			
Application Papers			:			
9) The specification is objected to by the Examina	er.		:			
10)⊠ The drawing(s) filed on <u>14 March 2002</u> is/are: a)⊠ accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the	e drawing(s) be held in abeyance. Se	e 37 CFR 1.85(a).				
Replacement drawing sheet(s) including the correct	ction is required if the drawing(s) is ob	jected to. See 37 CFF	R 1.121(d).			
11)☐ The oath or declaration is objected to by the E	xaminer. Note the attached Office	Action or form PTC	D-152.			
Priority under 35 U.S.C. § 119						
12)⊠ Acknowledgment is made of a claim for foreign	n priority under 35 U.S.C. & 119/a)-(d) or (f)	•			
a) ⊠ All b) □ Some * c) □ None of:	in priority under 55 5.5.5. § 175(a) (d) 01 (1).	:			
1. ☐ Certified copies of the priority documen	ts have been received		:			
2. Certified copies of the priority documen		ion No.				
3. Copies of the certified copies of the price	• •		Stage			
application from the International Burea	•		····			
* See the attached detailed Office action for a lis		∍d.	:			
Attachment(e)	•					
Attachment(s) 1) X Notice of References Cited (PTO-892)	4) Interview Summary	/ (PTO-413)				
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail D	ate				
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date <u>3/14/02</u> .	5) Notice of Informal F 6) Other:	Patent Application (PTO-	152)			

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DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless – (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-10 and 17 are rejected under 35 U.S.C. 102(b) as being anticipated by Valentine et al. (EP 0 285 834 A, published 10/12/88).

Regarding claim 1, Valentine et al. teaches a method of depositing $Hg_{1-x}Cd_xTe$ onto a substrate (column 4, lines 11-14), in a MOVPE technique (MOCVD, column 2, lines 43-46), where $0 \le x \le 1$, comprising the step of reacting together a volatile organotellurium compound and a volatile organocadmium compound (column 2, lines 43-49) and mercury vapor (column 3, lines 54-56); characterized in that the organotellurium compound is isopropylallyltelluride (claim 4 with 3 carbon atoms) and in that the substrate is maintained at a temperature in the range of 150°C to 350°C (column 4, lines 11-14).

Regarding claims 2 and 3, Valentine et al. teaches the method of depositing $Hg_{1-x}Cd_xTe$ according to claim 1, wherein the organocadmium compound is an alkyl cadmium compound, which is dimethyl cadmium (column 2, lines 43-49).

Regarding claims 4-6, Valentine et al. teaches the method of depositing $Hg_{1-x}Cd_xTe$ according to claim 1, wherein 0 < x < 1, x = 0, and x = 1 (column 2, lines 43-49).

Regarding claim 7, Valentine et al. teaches the method of depositing Hg_{1-x}Cd_xTe according to claim 6, wherein the reaction is carried out in the presence of mercury vapor (column 3, lines 54-56).

Regarding claim 8, Valentine et al. teaches the method of depositing Hg_{1-x}Cd_xTe according to claim 1, wherein the substrate comprises CdTe, GaAs, or Si.

Regarding claims 9 and 10, Valentine et al. teaches the method of depositing $Hg_{1-x}Cd_xTe$ according to claim 1, wherein the temperature of the substrate is maintained at a temperature in the range of 150°C to 300°C and 250°C to 300°C (column 4, lines 11-14).

Regarding claim 17, Valentine et al. teaches Hg_{1-x}Cd_xTe obtainable by a method according to claim 1 (column 4, lines 11-14).

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 11-16 are rejected under 35 U.S.C. 103(a) as being unpatentable over Valentine et al. (EP 0 285 834 A, published 10/12/88) in view of Ahlgren (U.S. 5,189,297).

Regarding claims 11-16, Valentine et al. teaches a method of fabricating an electronic device comprising the step of depositing Hg_{1-x}Cd_xTe onto a substrate by a method according to claim 1 (note 35 U.S.C. 102(b) rejection above), but does not

teach connecting at least two electrodes to the Hg_{1-x}Cd_xTe, doping the Hg_{1-x}Cd_xTe, doping the Hg_{1-x}Cd_xTe in such a manner than a p-n junction is formed, passivating the Hg_{1-x}Cd_xTe with a layer of CdTe, a device obtainable by a method according to claim 11, or an infrared detector comprising an array of devices, each device being obtainable by a method according to claim 11.

Ahlgren teaches a method of forming contacts on a layer of Hg_{1-x}Cd_xTe (column 7, lines 52-57; 92 in Fig. 5), doping Hg_{1-x}Cd_xTe (layers 14 and 16 in Fig. 1; column 3, lines 39-48) in such a manner that an array of p-n junction is formed (Figs. 1 and 5), and passivating the Hg_{1-x}Cd_xTe with CdTe (column 7, line 40-43).

Therefore, at the time of the invention, it would have been obvious to one of ordinary skill in the art to combine the teachings of Valentine et al. and Ahlgren by fabricating a device according to the process steps taught by Ahlgren (connecting at least two contacts to a layer of Hg_{1-x}Cd_xTe, doping the Hg_{1-x}Cd_xTe to form an array of pn junctions, and passivating the Hg_{1-x}Cd_xTe with a layer of CdTe), employing the method taught by Valentine et al. to deposit the layer of Hg_{1-x}Cd_xTe, which would result in a device obtainable by a method according to claim 11 and an infrared detector comprising an array of devices, each device being obtainable by a method according to claim 11.

The motivation for doing so at the time of the invention would have been that the method taught by Valentine et al. results in high-quality Hg_{1-x}Cd_xTe epitaxial films, as expressly taught by Valentine et al. (column 2, lines 46-49), which would result in the fabrication of a high-performance device.

Claim 18 is rejected under 35 U.S.C. 103(a) as being unpatentable over Valentine et al. (EP 0 285 834 A, published 10/12/88) in view of the basic organic chemistry textbook *Organic Chemistry*, Fourth Edition, written by Morrison et al.

Regarding claim 18, Valentine et al. teaches a method for the preparation of isopropylallyltelluride comprising the steps: (a) reacting a compound isopropyl lithium with Te, thereby producing isopropyl lithiumtelluride; and (b) reacting the isopropyl lithiumtelluride produced by step (a) with allyl chloride. Valentine et al. does not teach reacting the isopropyl lithiumtelluride produced by step (a) with allyl bromide.

Morrison et al. teaches in Table 1.3 (pg. 21) that allyl bromide has a weaker bond strength between carbon and bromine (165) than allyl choride has between carbon and chlorine (173).

Therefore, it would be obvious to one of ordinary skill in the art to modify the method for the preparation of isopropylallyltelluride taught by Valentine et al. by substituting allyl bromide for allyl chloride. The motivation for doing so at the time of the invention would have been that allyl bromide's weaker bond strength makes it easier to dissociate, and therefore more reactive, when reacted with isopropyl lithiumtelluride.

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Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Heather A. Doty, whose telephone number is 571-272-8429. The examiner can normally be reached on M-F, 8:30 - 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr., can be reached at 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Laura Mifeluly

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